L Number	Hits	Search Text	DB	Time stamp
1	1620	"dual damascene" and etch$3	USPAT; US-PGPUB; EPO; JPO	2002/07/19 09:40
6	110	("dual damascene" and etch$3) and "etch mask"	USPAT; US-PGPUB; EPO; JPO	2002/07/19 09:40
11	103	(("dual damascene" and etch$3) and "etch mask") and (vias via trenches trench)	USPAT; US-PGPUB; EPO; JPO	2002/07/19 09:42
16	101	((("dual damascene" and etch$3) and "etch mask") and (vias via trenches trench)) and pattern$3	USPAT; US-PGPUB; EPO; JPO	2002/07/19 09:42
21	39	(((("dual damascene" and etch$3) and "etch mask") and (vias via trenches trench)) and pattern$3) and "low k"	USPAT; US-PGPUB; EPO; JPO	2002/07/19 09:49
26	1511	convert$3 near6 dielectric	USPAT; US-PGPUB; EPO; JPO	2002/07/19 09:54
31	452	(convert$3 near6 dielectric) and etch$	USPAT; US-PGPUB; EPO; JPO	2002/07/19 09:55
36	59	((convert$3 near6 dielectric) and etch$) and ("etch mask" "etch stop")	USPAT; US-PGPUB; EPO; JPO	2002/07/19 09:55